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INFORMATION DISCLOSURE STATEMENT (use several sheets if necessary)		ATM-515		10015326			
IDC US Ref 16		FILING DATE		December 13, 2001		GROUP	
TBA							
U.S. PATENT DOCUMENTS							
EXAMINER INITIAL	PATENT NUMBER	ISSUE DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
AA	5,204,134	4/20/1993	Klein, et al.				
AB	5,536,323	7/16/1996	Klein, et al.				
AC	5,711,816	1/27/1998	Klein, et al.				
AD	6,171,943	12/9/2002	Mandal, et al.			01/09/2001	
AE	4,745,169	3/17/1988	Sugiyama, et al.				
AF	4,733,370	7/3/1988	Kray, et al.				
AG	6,114,500	8/3/2000	Mod, et al.				
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AP	5,804,040	9/3/1998	Asai, et al.				
FOREIGN PATENT DOCUMENTS							
DOCUMENT NUMBER	PUBLICATION DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES NO		
AQ	JP 50-111198	Japan			X		
					(abstract only)		
					X		
OTHER DOCUMENTS (Including Abstract, Title, Journal Data, Page Number, Etc.)							
AR	Nishimura, et al., "Thermolysis of Polyhedral Oligomeric Silsesquioxane (POSS) Macromonomers and POSS-Siloxane Copolymers", Chem. Mater., 1996, 8, pp. 1250-1259.						
AS	Evel K. Laxman, Neil Hendrix Barry Arkes, Terry A. Tabler "Synthesizing Low-K CVD Materials for Fab Use" Semiconductor International, 11/1/2000						
Continue on Page							
EXAMINER T. Manshawn				DATE CONSIDERED 2/24/03			
EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.							

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